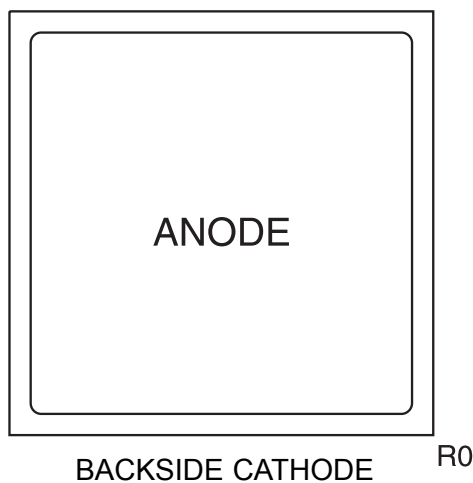


PROCESS DETAILS

| | |
|------------------------|------------------|
| Process | EPITAXIAL PLANAR |
| Die Size | 52 X 52 MILS |
| Die Thickness | 9 MILS |
| Anode Bonding Pad Area | 47 X 47 MILS |
| Top Side Metalization | Al - 20,000Å |
| Back Side Metalization | Au - 10,000Å |

GEOMETRY



GROSS DIE PER 4 INCH WAFER

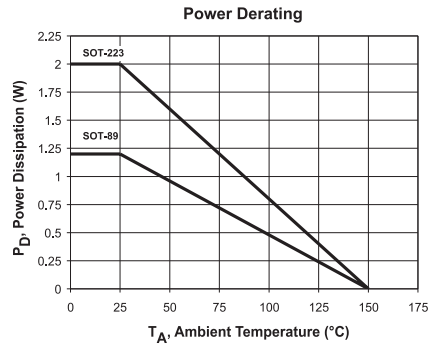
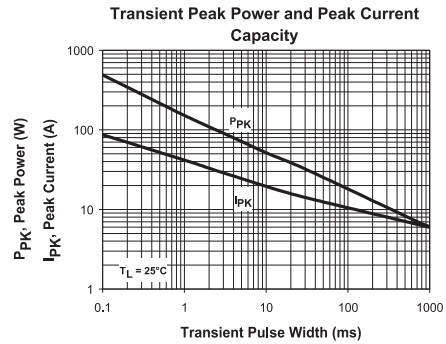
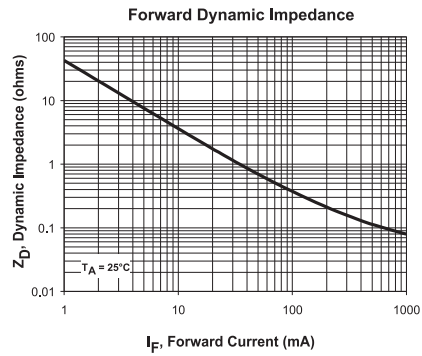
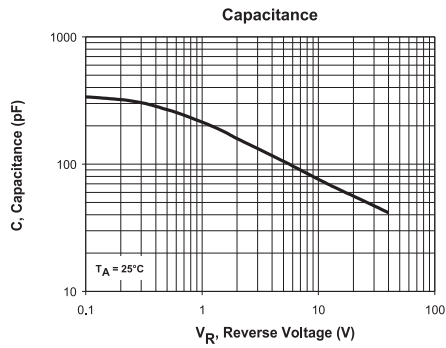
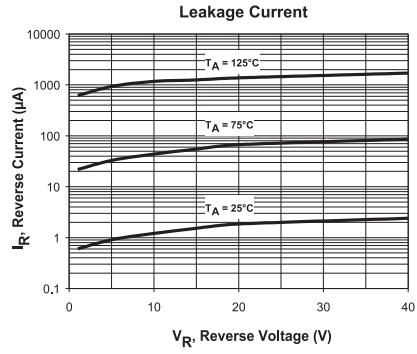
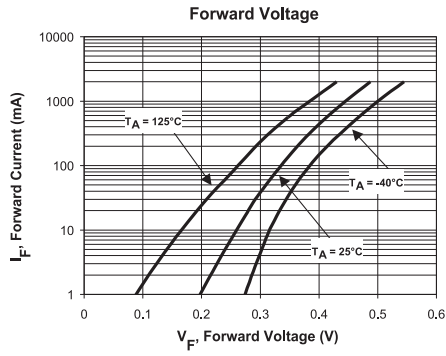
5,110

PRINCIPAL DEVICE TYPES

1N5817
1N5818
1N5819
CXSH-4
CZSH-4

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